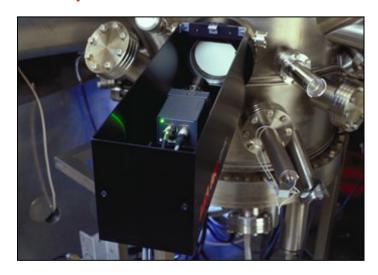


kSA 400 Phase Locked Epitaxy (PLE) Plug-In

Multi-layer MBE Growth Control via RHEED Analysis and Shutter Control

The kSA 400 PLE plug-in option automatically controls layer-by-layer growth by using real-time monitoring of Reflection High Energy Electron Diffraction (RHEED) oscillations to automate shutter open and close times. This yields atomic-level accuracy and reproducible results for thin films. The PLE plug-in option combines a highly sophisticated PLE algorithm, programmable Process Table, and digital I/O board, all seamlessly integrated into the kSA 400 environment.



Features

- Highly sophisticated PLE algorithm continuously monitors 1st derivative of real-time intensity data; eliminates noise and transients.
- Peaks, valleys, or both peaks and valleys can be phase-locked.
- Timed growth control is available when intensity oscillations are absent.
- Programmable process table: up to 8 processes, 1000 cycles, and delay/recovery timing for complete growth recipes with advanced processes.
- 8-channel digital I/O board and cabling enables software-controlled shutters (open/close).
- External triggering allows for synchronized PLE with high speed substrate rotation.

Simple Software and User Interface | State | Color |

Your partner in thin-film metrology

k-Space Associates, Inc., is a leading supplier to the surface science and thin-film technology industries. Since 1992, we've delivered the most advanced thin-film metrology tools and software thanks to close collaboration with our worldwide customer base.

kSA 400 Phase Locked Epitaxy (PLE) May 28, 2021